

# Making integrated circuits

2014-03-20, Carsten Wulff

# Topic for today

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- How do we make integrated circuits
- What to focus on the next five years

# Who am I

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- Carsten Wulff
- Senior R & D engineer at Nordic Semiconductor (3 days a week)
- Post. doc at NTNU (2 days a week)
- Married with three kids
- Master (2002), Ph.D (2008)

# What do I do at Nordic?

Analog integrated circuit design,  
mostly analog to digital  
converters



## nRF51822

Multiprotocol *Bluetooth*® 4.0 low energy/2.4 GHz RF SoC

### Product Specification v1.1

#### Key Features

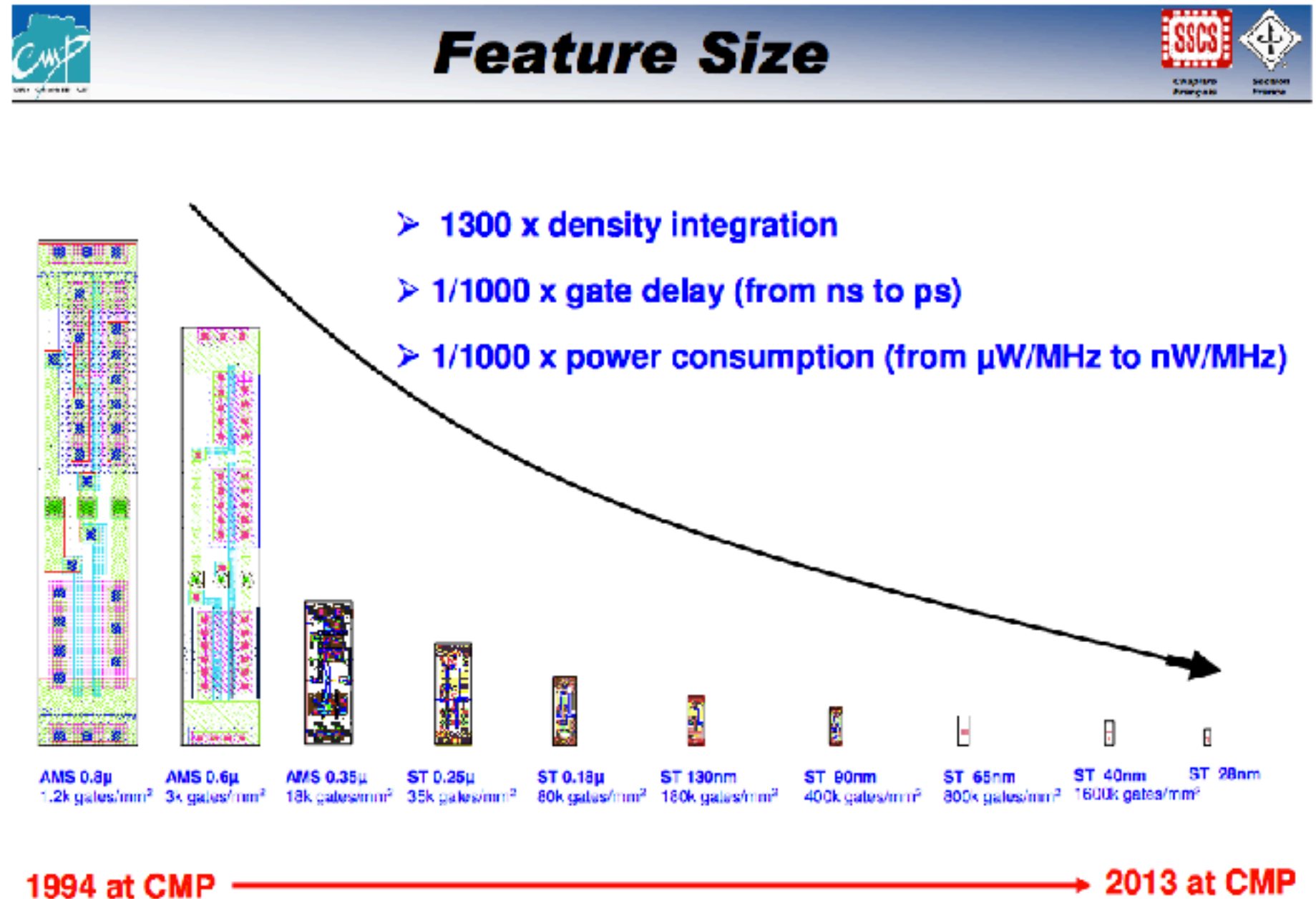
- 2.4 GHz transceiver
  - -93 dBm sensitivity *Bluetooth*® low energy
  - 250 kbps, 1 Mbps, 2 Mbps supported data rates
  - TX Power -20 to +4 dBm in 4 dB steps
  - TX Power -30 dBm Whisper mode
  - 13 mA peak RX, 10.5 mA peak TX (0 dBm)
  - RSSI (1 dB resolution)
- ARM® Cortex™-M0 32 bit processor
  - 275 µA/MHz running from flash memory
  - 150 µA/MHz running from RAM
  - Serial Wire Debug (SWD)
- S100 series SoftDevice ready
- Memory
  - 256 kB or 128 kB embedded flash program memory
  - 16 kB RAM
- Support for non-concurrent multiprotocol operation
  - On-air compatibility with nRF24L series
- Flexible Power Management
  - Supply voltage range 1.8 V to 3.6 V
  - 2.5 µs fast wake-up using 16 MHz RCOSC
  - 0.4 µA @ 3 V OFF mode
  - 0.5 µA @ 3 V in OFF mode + 1 region RAM retention
  - 2.3 µA @ 3 V ON mode, all blocks IDLE
- 8/9/10 bit ADC - 8 configurable channels
- 31 General Purpose I/O Pins
- Two 16 bit and one 32 bit timers with counter mode
- SPI Master

#### Applications

- Computer peripherals and
  - Mouse
  - Keyboard
  - Multi-touch
- Interactive entertainment
  - Remote control
  - 3D Glasses
  - Gaming controller
- Personal Area Networks
  - Health and fitness monitor devices
  - Medical devices
  - Key-fobs + trackers
- Remote control toys

# What do I do at NTNU?

Analog to digital converters in advanced CMOS technologies.



CMP annual users meeting, 17 January 2013, PARIS

How do we make  
integrated circuits?

# Transistor

# 1947: First transistor

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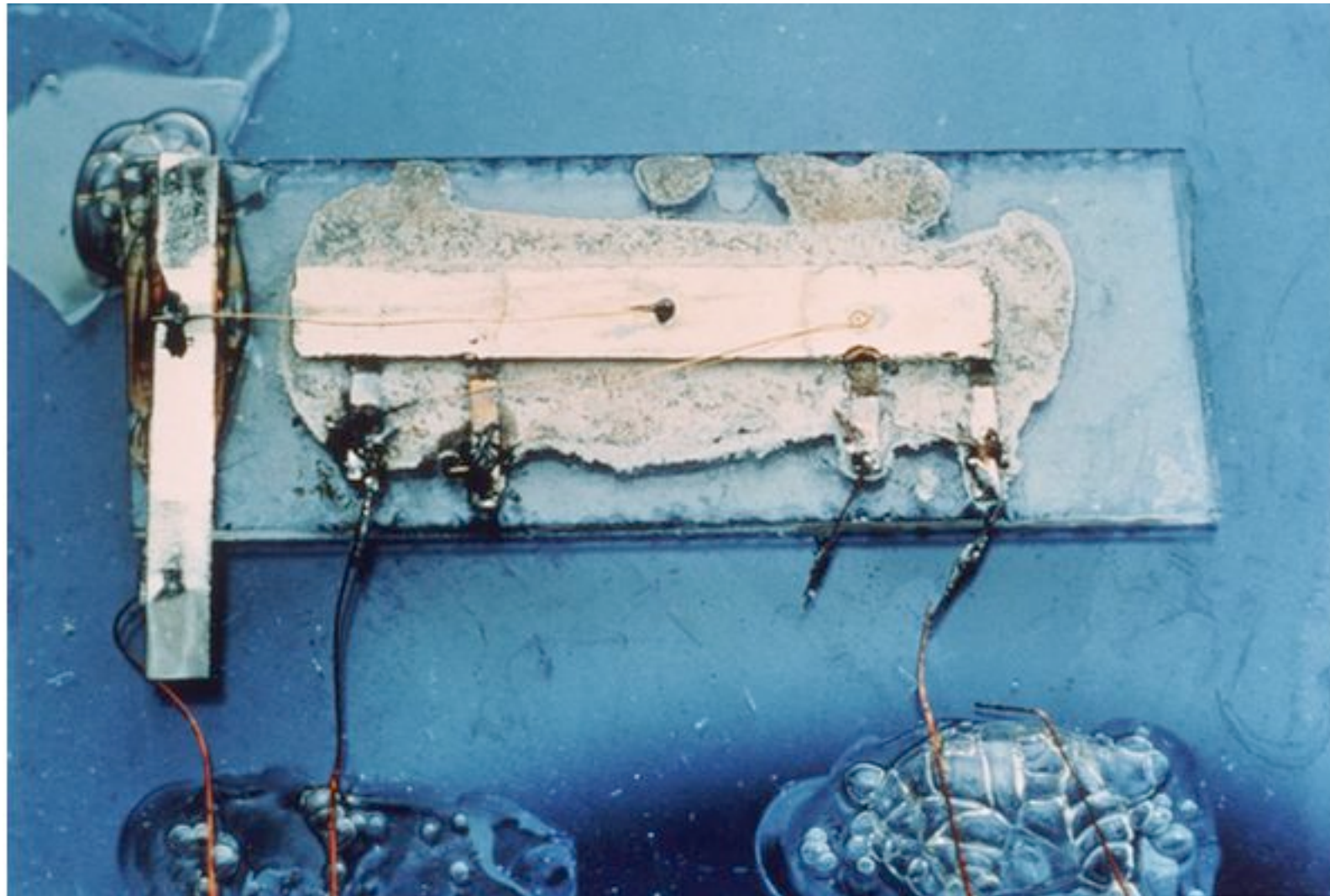


[http://www.beatriceco.com/bti/porticus/bell/bellabs\\_transistor.html](http://www.beatriceco.com/bti/porticus/bell/bellabs_transistor.html)



# 1958: Integrated circuit

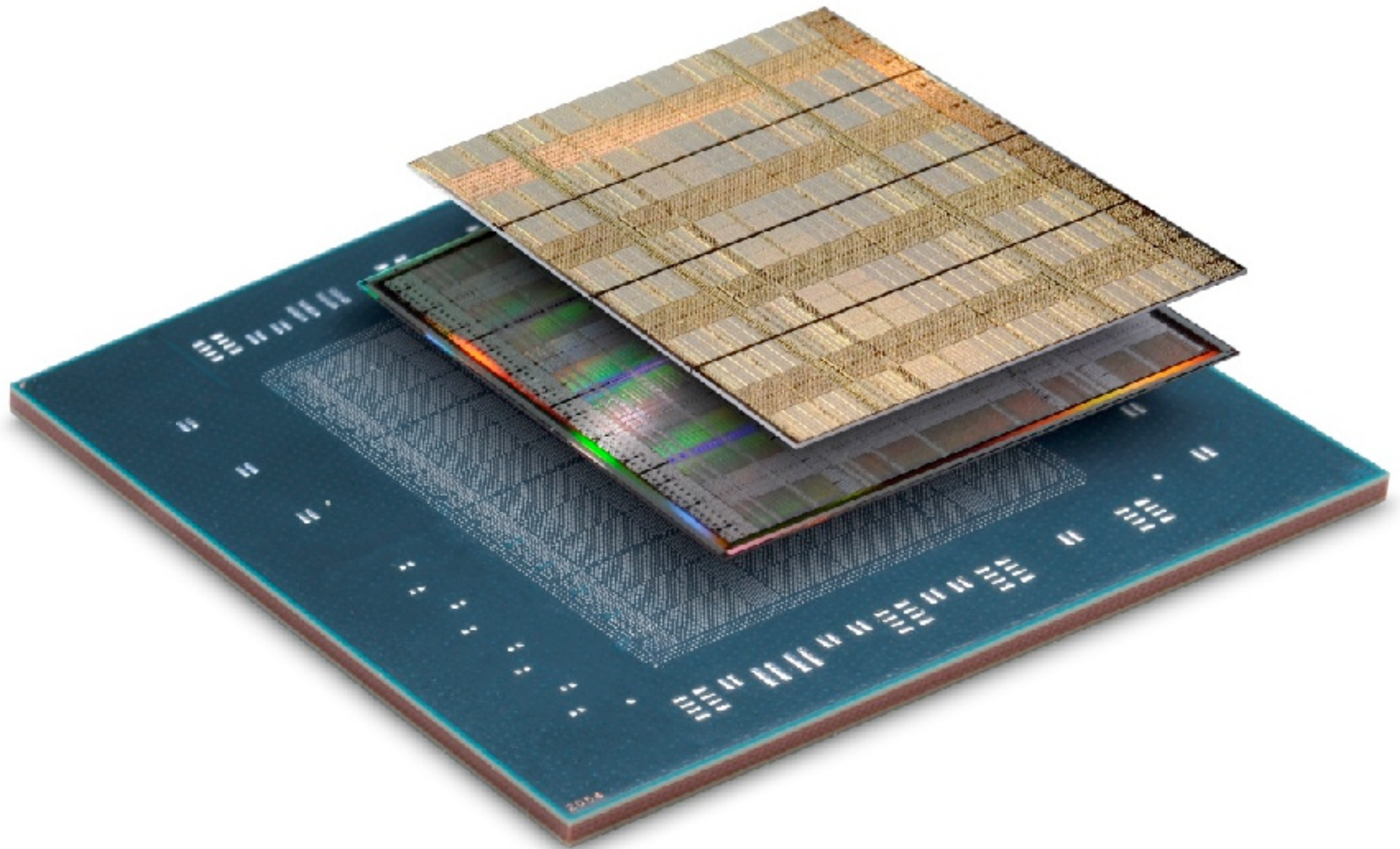
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[http://en.wikipedia.org/wiki/Jack\\_Kilby](http://en.wikipedia.org/wiki/Jack_Kilby)

# Xilinx Virtex-7

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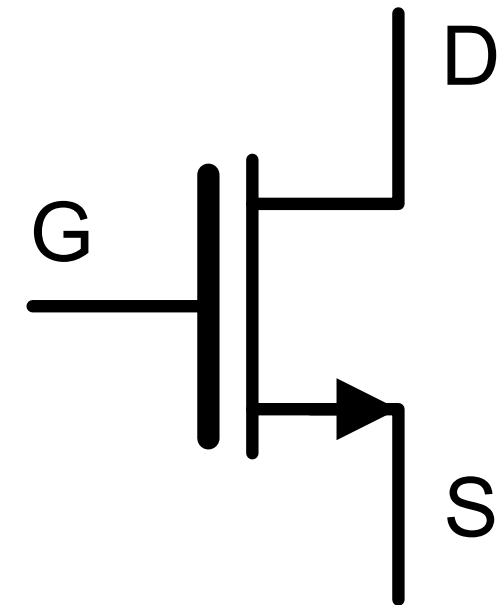


**6.8 Billion transistors**



# Transistor

- The most important device in an integrated circuit.
- An extremely complicated device
- Need computer models to describe the behavior accurately.
- BSIM model published in 1987, 17 parameters to describe a transistor. This is similar what you find in textbooks. Applies to 1um transistor lengths.



458

IEEE JOURNAL OF SOLID-STATE CIRCUITS, VOL. 22, NO. 4, AUGUST 1987

## BSIM: Berkeley Short-Channel IGFET Model for MOS Transistors

BING J. SHEU, MEMBER, IEEE, DONALD L. SCHIARFETTER, FELLOW, IEEE, PING-KEUNG KO, MEMBER, IEEE, AND MIN-CHIE JENG

**Abstract**—The Berkeley Short-channel IGFET Model (BSIM), an accurate and computationally efficient MOS transistor model, and its associated characterization facility for advanced integrated-circuit design are described. Both the strong-inversion and weak-inversion components of the drain-current expression are included. In order to speed up the circuit-simulation execution time, the dependence of the drain current on the substrate bias has been modeled with a numerical approximation. This approximation also simplifies the transistor terminal charge expressions. The charge model was derived from its drain-current counterpart to

only as accurate as the models used. In the past, the SPICE2 program has provided three built-in MOS transistor models [6]. The Level-1 model, which contains fairly simple expressions, is most suitable for preliminary analysis. The Level-2 model, which contains expressions from detailed device physics, does not work well for small-geometry transistors. The Level-3 model represents an attempt to pursue the semi-empirical modeling approach

3. *Saturation Region* [ $V_{GS} > V_{th}$  and  $V_{DS} \geq V_{DSAT}$ ]:

$$I_{DS} = \frac{\mu_0}{[1 + U_0(V_{GS} - V_{th})]} \cdot \frac{C_{ox} \frac{W}{L} (V_{GS} - V_{th})^2}{2aK}$$

# BSIM 4.5 = 284 parameters

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.MODEL N1 NMOS LEVEL=14 VERSION=4.5.0 BINUNIT=1 PARAMCHK=1 MOBMOD=0 CAPMOD=2 IGCMOD=1 IGBMOD=1 GEOMOD=1  
DIOMOD=1 RDSMOD=0 RBODYMOD=0 RGATEMOD=3 PERMOD=1 ACNQSMOD=0 TRNQSMOD=0 TEMPMOD=0 TNOM=27  
**TOXE=1.8E-009** TOXP=10E-010 TOXM=1.8E-009 DTOX=8E-10 EPSROX=3.9 WINT=5E-009 LINT=1E-009 LL=0 WL=0 LLN=1 WLN=1 LW=0  
WW=0 LWN=1 WWN=1 LWL=0 WWL=0 XPART=0 TOXREF=1.4E-009 SAREF=5E-6 SBREF=5E-6 WLOD=2E-6 KU0=-4E-6 KVSAT=0.2  
KVTH0=-2E-8 TKU0=0.0 LLODKU0=1.1 WLODKU0=1.1 LLODVTH=1.0 WLODVTH=1.0 LKU0=1E-6 WKU0=1E-6 PKU0=0.0 LKVTH0=1.1E-6  
WKVTH0=1.1E-6 PKVTH0=0.0 STK2=0.0 LODK2=1.0 STETA0=0.0 LODETA0=1.0 LAMBDA=4E-10 VSAT=1.1E 005 VTL=2.0E5 XN=6.0 LC=5E-9  
RNOIA=0.577 RNOIB=0.37 LINTNOI=1E-009 WPEMOD=0 WEB=0.0 WEC=0.0 KVTHOWE=1.0 K2WE=1.0 KUOWE=1.0 SCREF=5.0E-6  
TVOFF=0.0 TVFBSDOFF=0.0 **VTH0=0.25** K1=0.35 K2=0.05 K3=0 K3B=0 W0=2.5E-006 DVT0=1.8 DVT1=0.52 DVT2=-0.032 DVT0W=0  
DVT1W=0 DVT2W=0 DSUB=2 MINV=0.05 VOFFL=0 DVTP0=1E-007 DVTP1=0.05 LPE0=5.75E-008 LPEB=2.3E-010 XJ=2E-008 NGATE=5E  
020 NDEP=2.8E 018 NSD=1E 020 PHIN=0 CDSC=0.0002 CDSCB=0 CDSCD=0 CIT=0 VOFF=-0.15 NFACTOR=1.2 ETA0=0.05 ETAB=0  
UC=-3E-011 VFB=-0.55 **U0=0.032** UA=5.0E-011 UB=3.5E-018 A0=2 AGS=1E-020 A1=0 A2=1 B0=-1E-020 B1=0 KETA=0.04 DWG=0 DWB=0  
PCLM=0.08 PDIBLC1=0.028 PDIBLC2=0.022 PDIBLCB=-0.005 DROUT=0.45 PVAG=1E-020 DELTA=0.01 PSCBE1=8.14E 008 PSCBE2=5E-008  
RSH=0 RDSW=0 RSW=0 RDW=0 FPROUT=0.2 PDITS=0.2 PDITSD=0.23 PDITSL=2.3E 006 RSH=0 RDSW=50 RSW=150 RDW=150  
RDSWMIN=0 RDWMIN=0 RSWMIN=0 PRWG=0 PRWB=6.8E-011 WR=1 ALPHA0=0.074 ALPHA1=0.005 BETA0=30 AGIDL=0.0002  
BGIDL=2.1E 009 CGIDL=0.0002 EGIDL=0.8 AIGBACC=0.012 BIGBACC=0.0028 CIGBACC=0.002 NIGBACC=1 AIGBINV=0.014 BIGBINV=0.004  
CIGBINV=0.004 EIGBINV=1.1 NIGBINV=3 AIGC=0.012 BIGC=0.0028 CIGC=0.002 AIGSD=0.012 BIGSD=0.0028 CIGSD=0.002 NIGC=1  
POXEDGE=1 PIGCD=1 NTOX=1 VFBSDOFF=0.0 XRCRG1=12 XRCRG2=5 CGSO=6.238E-010 CGDO=6.238E-010 CGBO=2.56E-011  
CGDL=2.495E-10 CGSL=2.495E-10 CKAPPAS=0.03 CKAPPAD=0.03 ACDE=1 MOIN=15 NOFF=0.9 VOFFCV=0.02 KT1=-0.37 KT1L=0.0  
KT2=-0.042 UTE=-1.5 UA1=1E-009 UB1=-3.5E-019 UC1=0 PRT=0 AT=53000 FNOIMOD=1 TNOIMOD=0 JSS=0.0001 JSWS=1E-011  
JSWGS=1E-010 NJS=1 IJTHSFWD=0.01 IJTHSREV=0.001 BVS=10 XJBVS=1 JSD=0.0001 JSWD=1E-011 JSWGD=1E-010 NJD=1  
IJTHDFWD=0.01 IJTHDREV=0.001 BVD=10 XJBVD=1 PBS=1 CJS=0.0005 MJS=0.5 PBSWS=1 CJSWS=5E-010 MJSWS=0.33 PBSWGS=1  
CJSWGS=3E-010 MJSWGS=0.33 PBD=1 CJD=0.0005 MJD=0.5 PBSWD=1 CJSWD=5E-010 MJSWD=0.33 PBSWGD=1 CJSWGD=5E-010  
MJSWGD=0.33 TPB=0.005 TCJ=0.001 TPBSW=0.005 TCJSW=0.001 TPBSWG=0.005 TCJSWG=0.001 XTIS=3 XTID=3 DMCG=0E-006  
DMCI=0E-006 DMDG=0E-006 DMCGT=0E-007 DWJ=0.0E-008 XGW=0E-007 XGL=0E-008 RSHG=0.4 GBMIN=1E-010 RBPB=5 RBPD=15  
RBPS=15 RBDB=15 RBSB=15 NGCON=1 JTSS=1E-4 JTSD=1E-4 JTSSWS=1E-10 JTSSWD=1E-10 JTSSWGS=1E-7 JTSSWGD=1E-7 NJTS=20.0  
NJTSSW=20 NJTSSWG=6 VTSS=10 VTSD=10 VTSSWS=10 VTSSWD=10 VTSSWGS=2 VTSSWGD=2 XTSS=0.02 XTSD=0.02 XTSSWS=0.02  
XTSSWD=0.02 XTSSWGS=0.02 XTSSWGD=0.02

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1.2 Poly-Silicon Gate Depletion .....	5.7.3 Substrate Current Induced Body Effect (SCBE) .....	9.1.2 AC Model .....	13.2 Temperature Dependence of Mobility.....
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3.1 Channel Charge Model .....	6.2 $I_{GIDL}$ and $I_{GIDL}$ Model .....	10.1 Flicker Noise Models .....	14.1.1 Mobility-related Equations.....
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# Lesson 1

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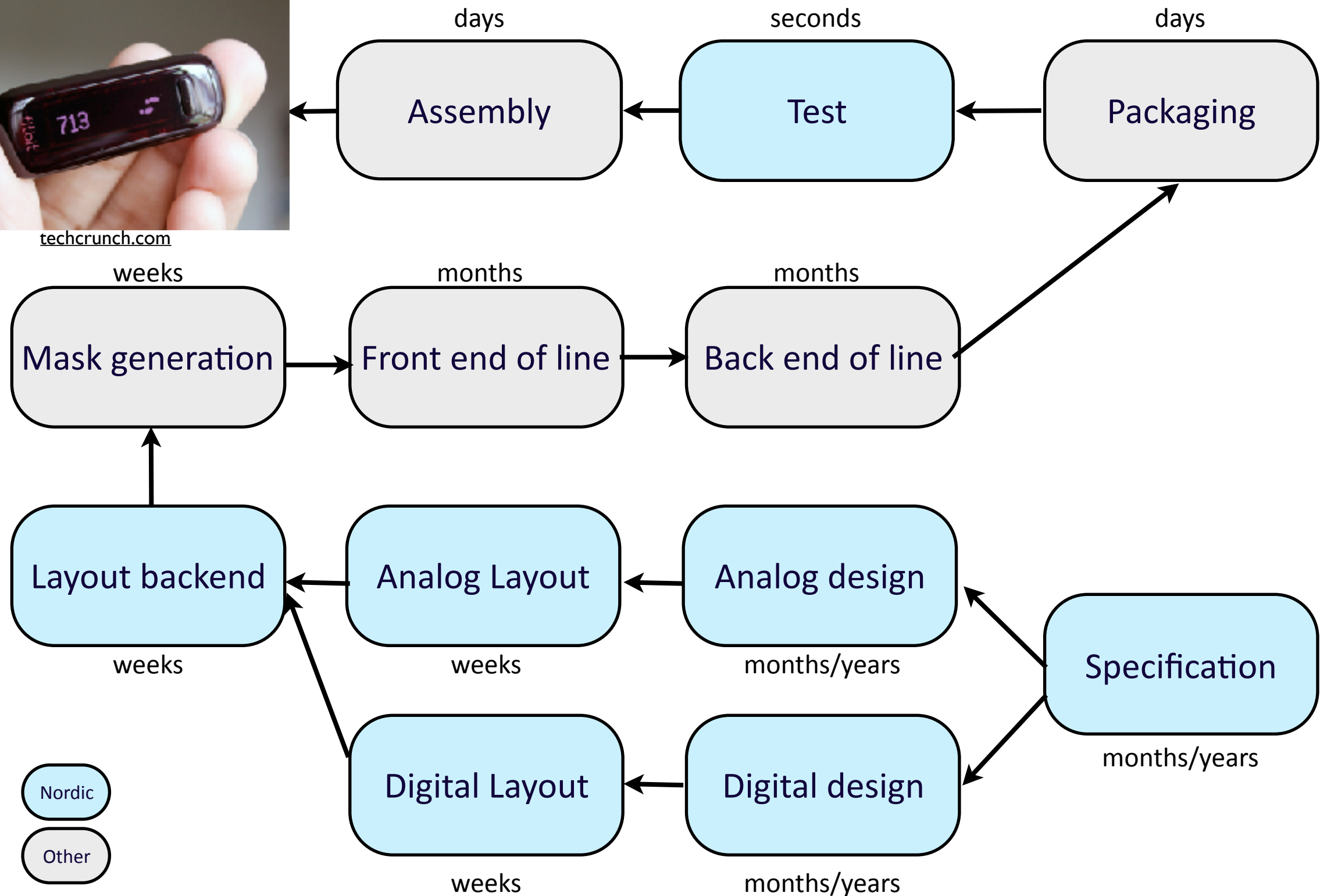
It's not practical to do accurate hand calculation for transistors. Finding where to start will have to do

**The story**

# The complete story



techcrunch.com





# Specification

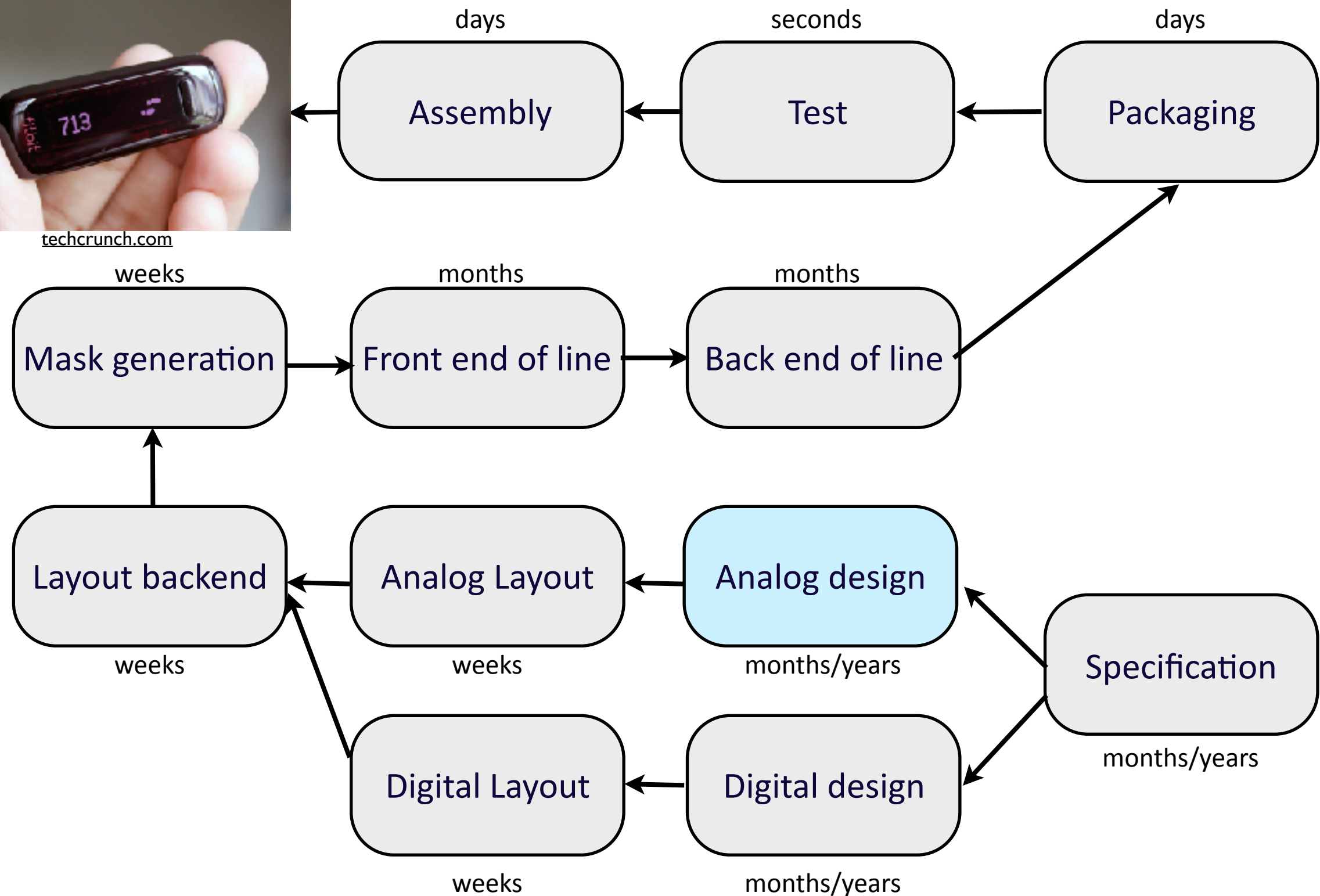
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- Trying to figure out what we need to make
- Maybe the most difficult step in the process, because were trying to guess what customers need 2-3 years before they need it.
- Usually done by the senior designers

# The complete story



[techcrunch.com](http://techcrunch.com)



## Demo: Design of an analog-to-digital converter

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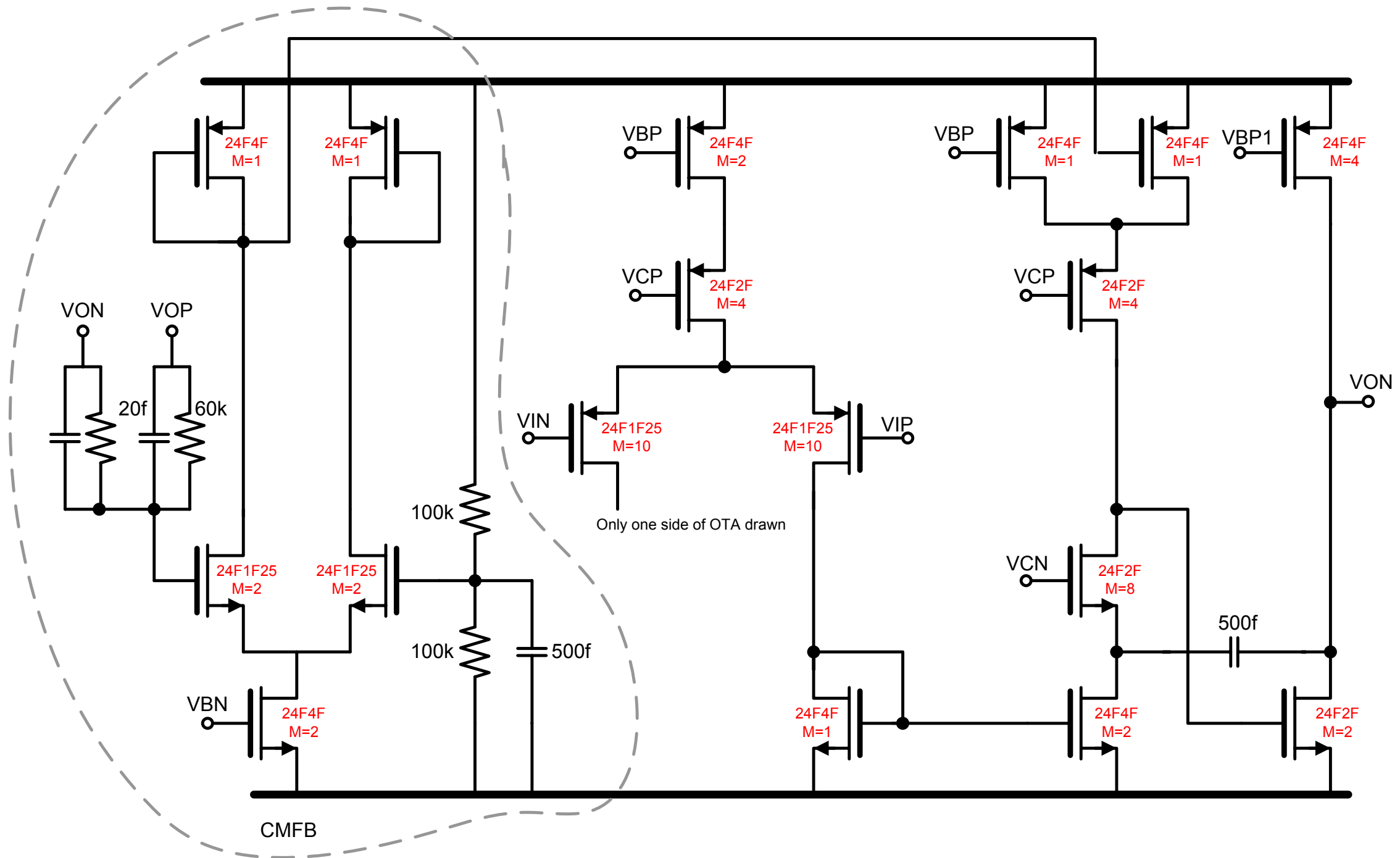
- 8-bit converter
- Does not need to be fast (kHz)
- Current is not that important (300uA)
- It must be small
- Must use 16MHz clock

# Transistor design tips

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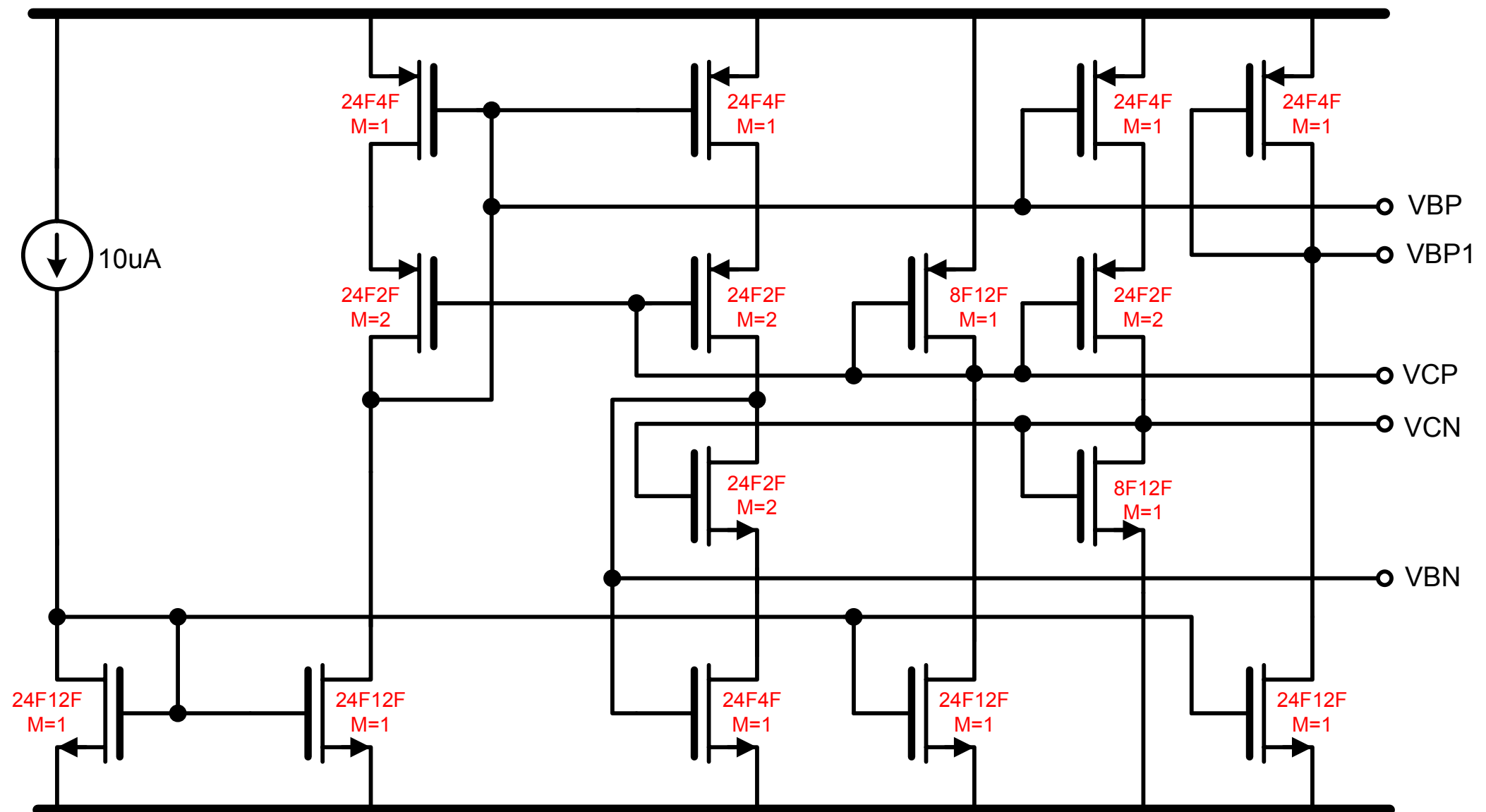
- NMOS  $\sim 2\mu\text{A} - 10\mu\text{A}$  per square. For example  $W=20F$   $L=2F \sim 100\mu\text{A}$  ( $F$  = minimum gate length)
- PMOS  $\sim 0.5\mu\text{A} - 3\mu\text{A}$  per square
- Width  $\sim 1 - 20$  times the lengths

# Differential OTA with CT CMFB

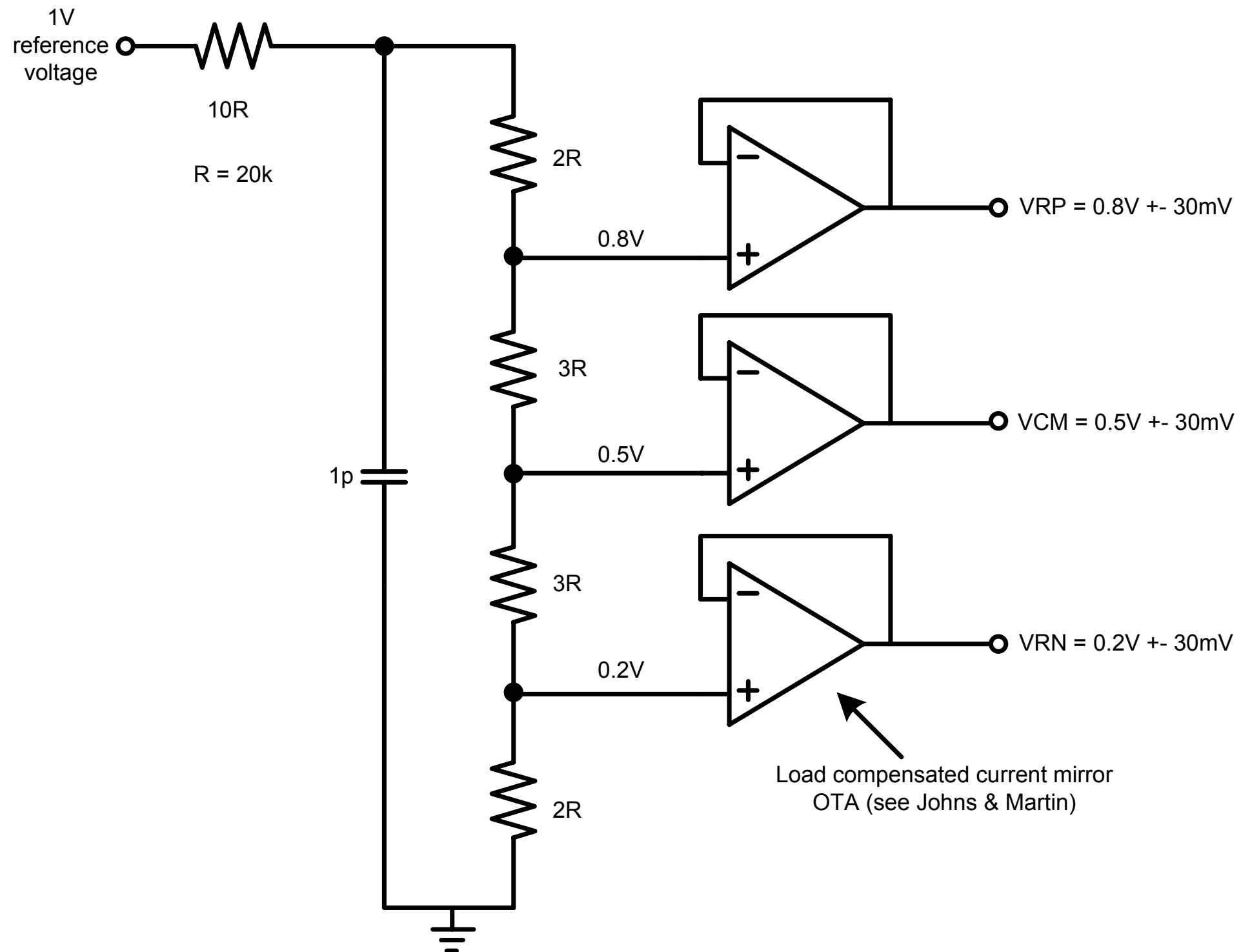


F = minimum transistor gate length. For example 24F4F => W = 24 x min gate, L = 4 x min gate

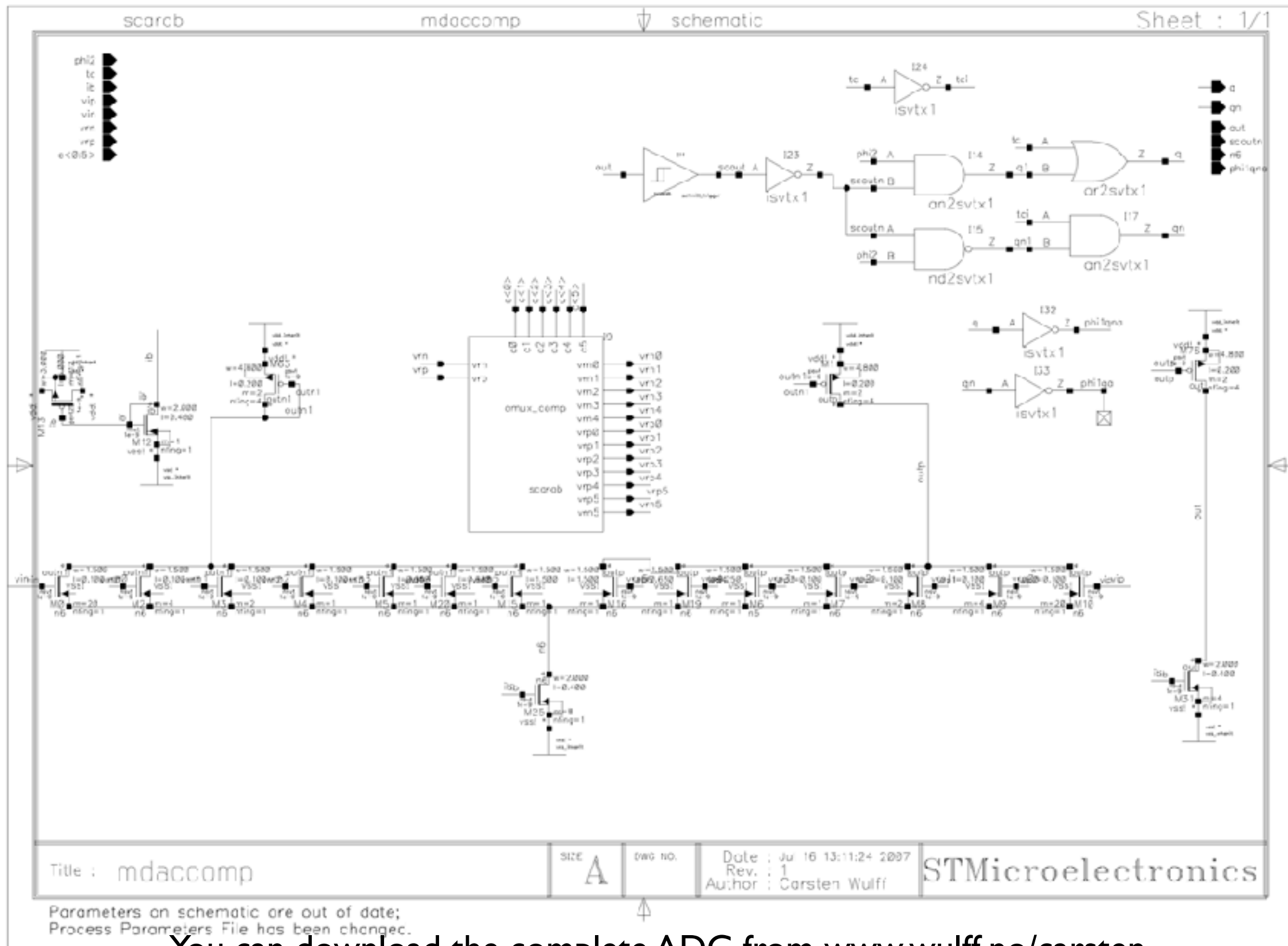
# Differential OTA - Bias circuit



# Voltage divider



# Schematic



You can download the complete ADC from [www.wulff.no/carsten](http://www.wulff.no/carsten)



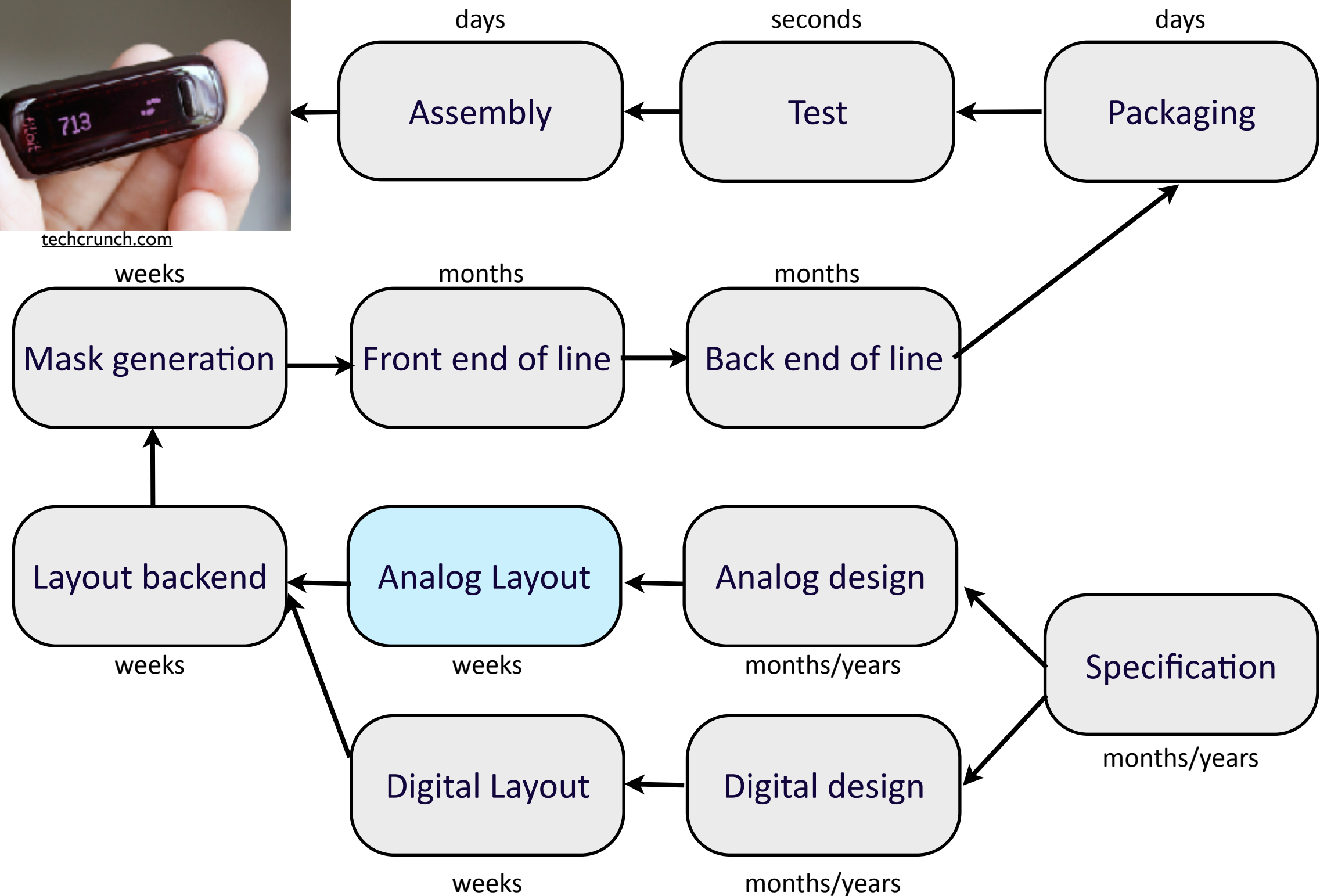
# Netlist

[illegible]

# The complete story



[techcrunch.com](http://techcrunch.com)



# Transistor layout - Diffusion

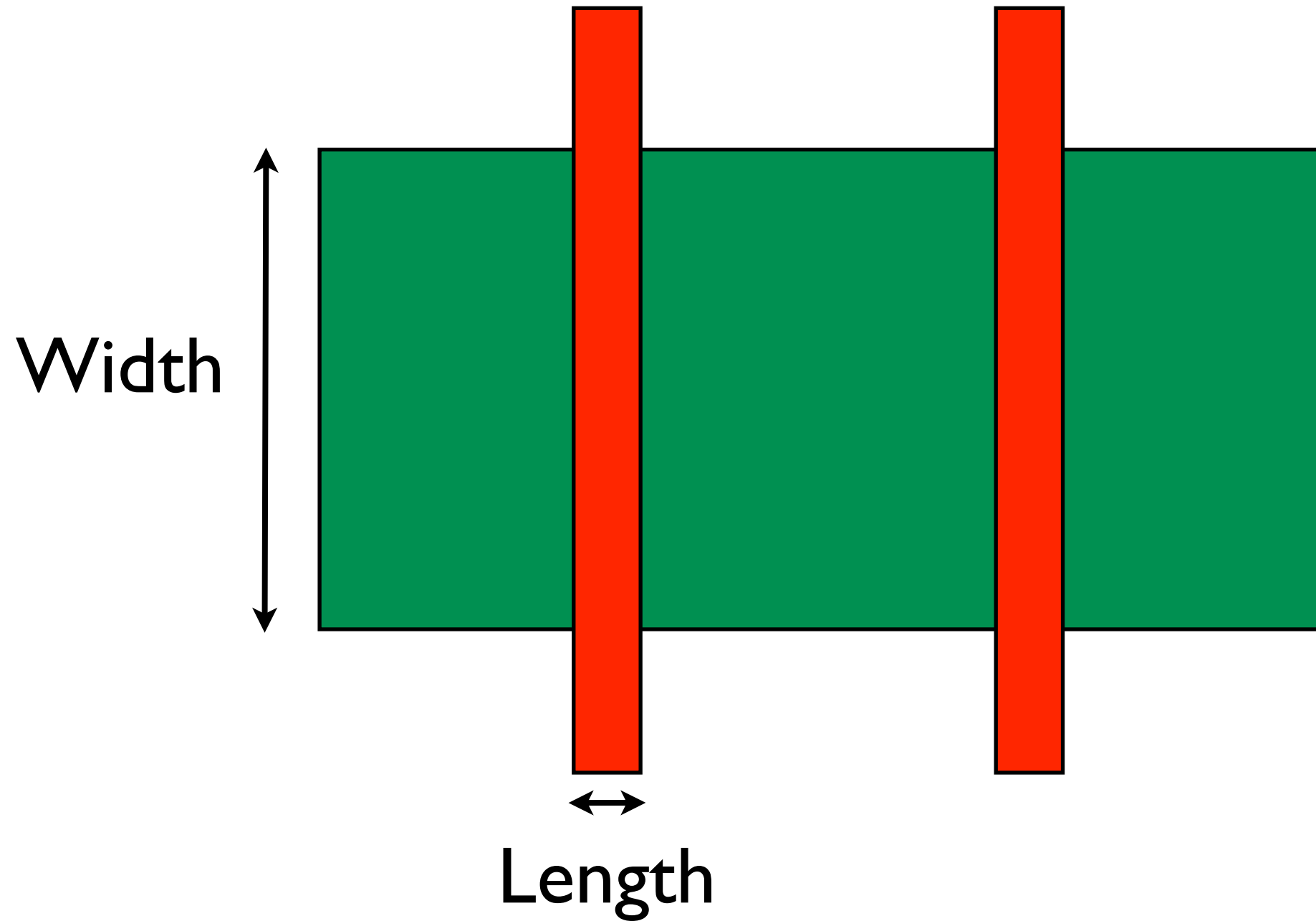
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Marks the boundary of a transistor

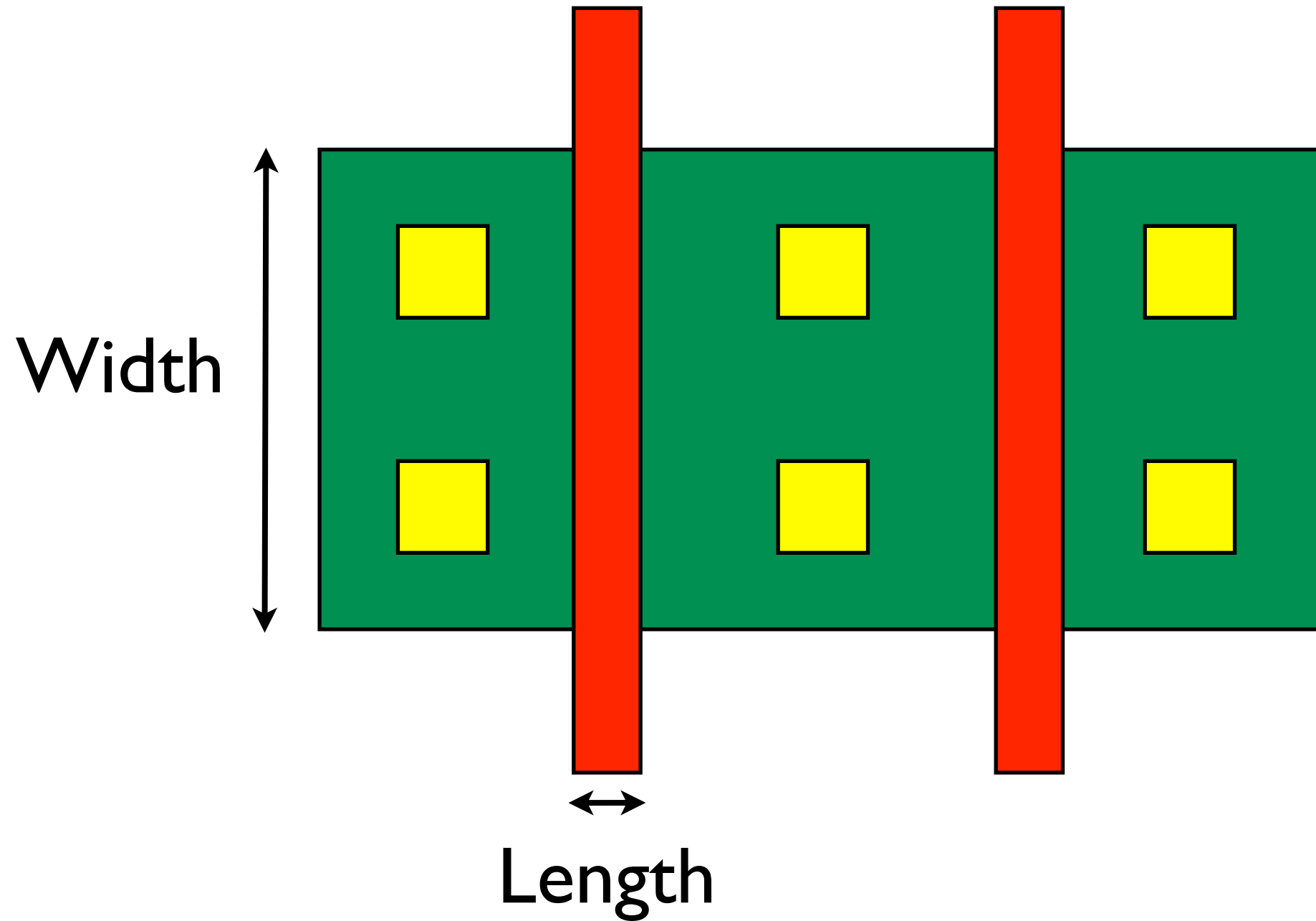
# Transistor layout - Gate

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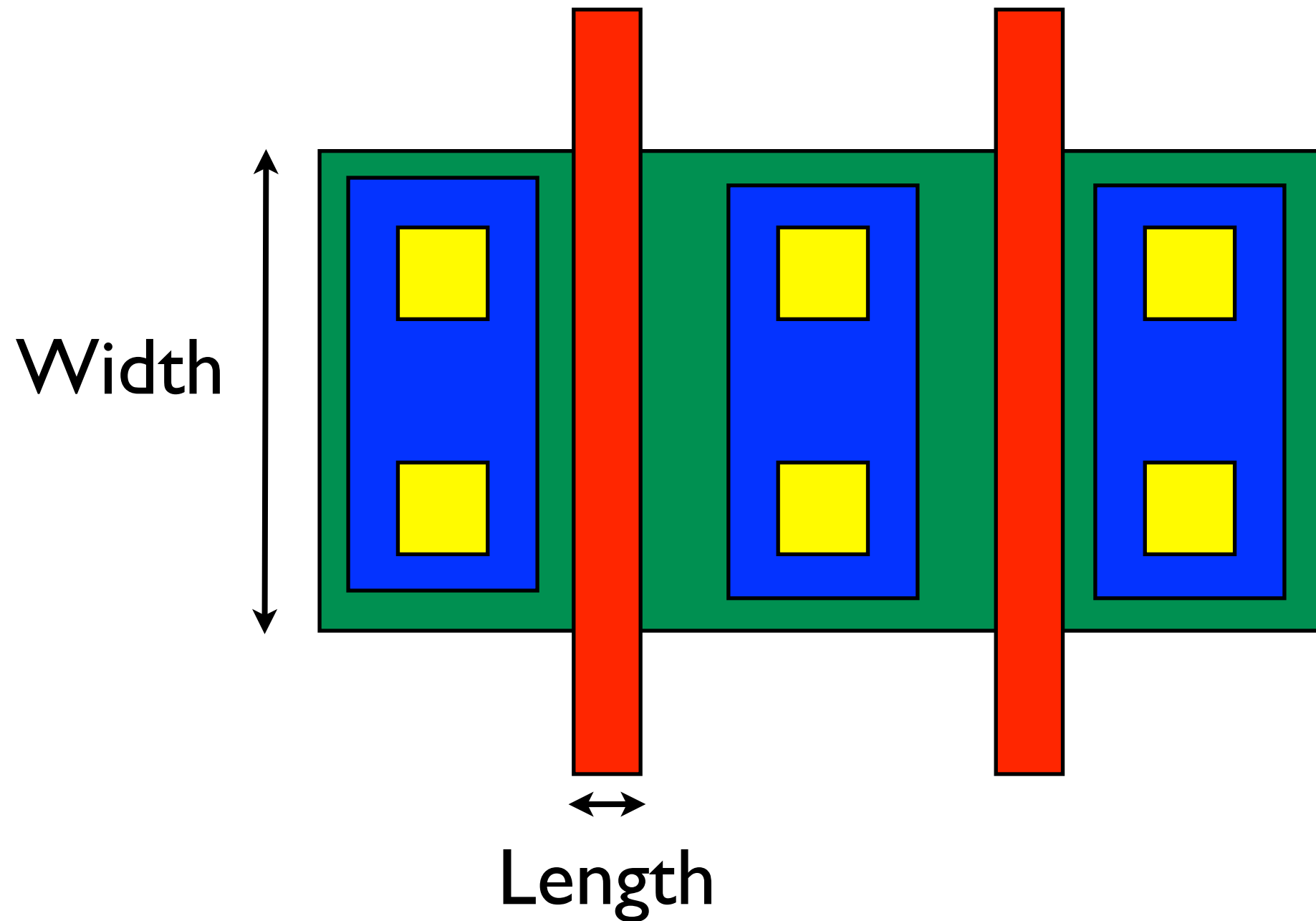
# Transistor layout - Contacts

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# Transistor layout - Metal 1

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# Current mirror operational transconductance amplifier

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Red = Poly silicon

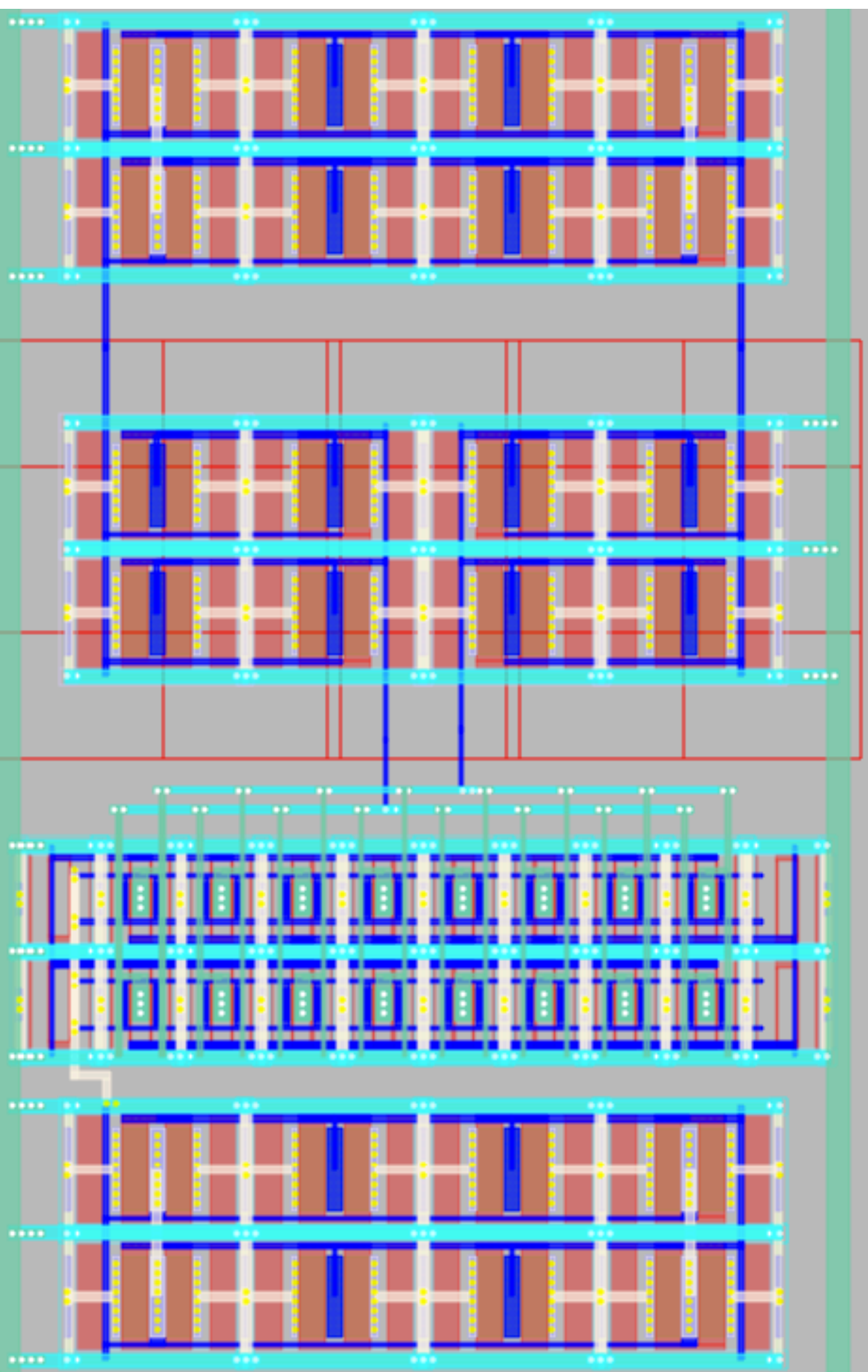
Yellow = contacts/via

Blue = Metal 1

Yellow = Metal 2

Turquoise = Metal 3

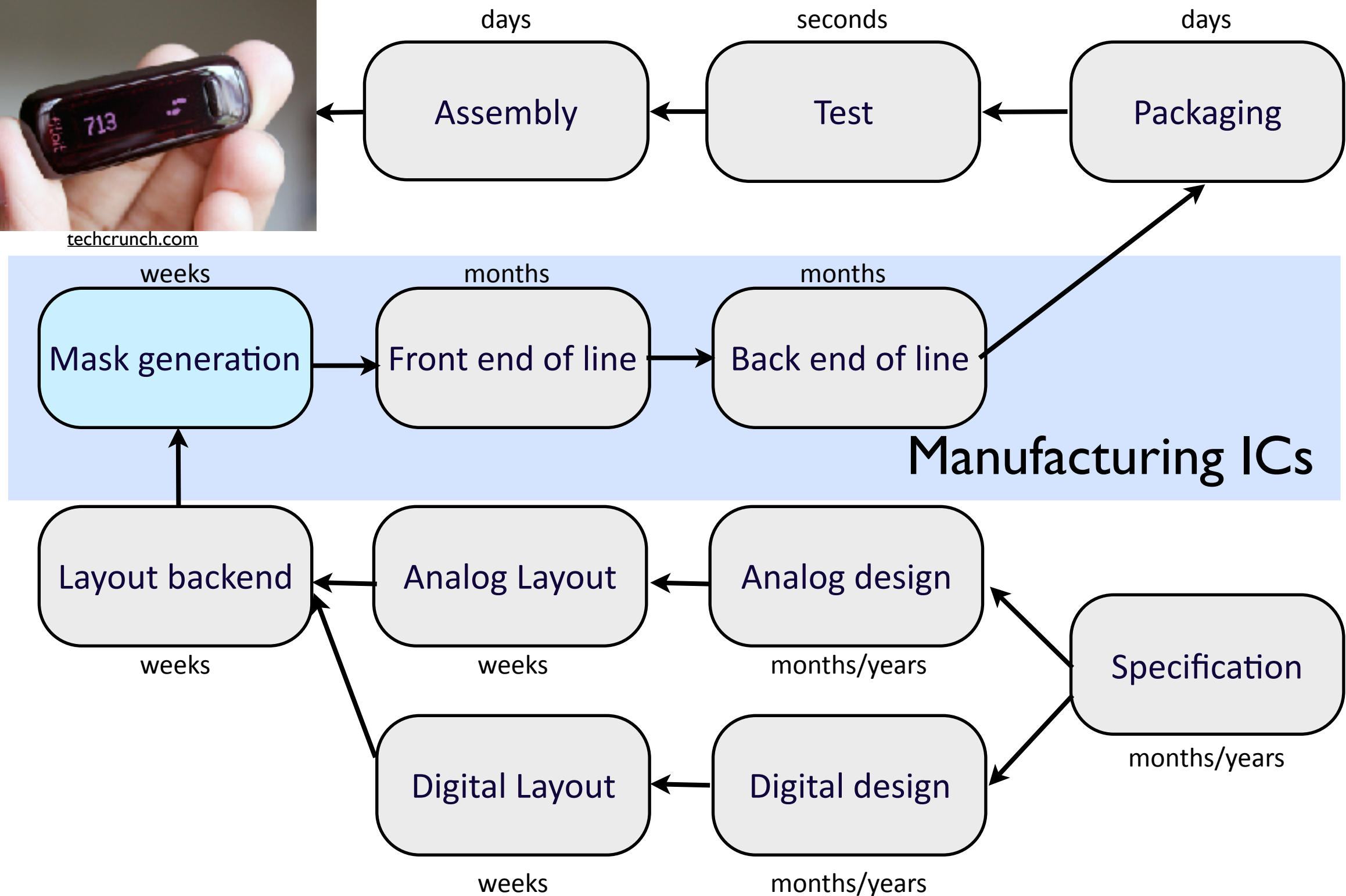
Green = Metal 4



# The complete story



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# Manufacturing ICs

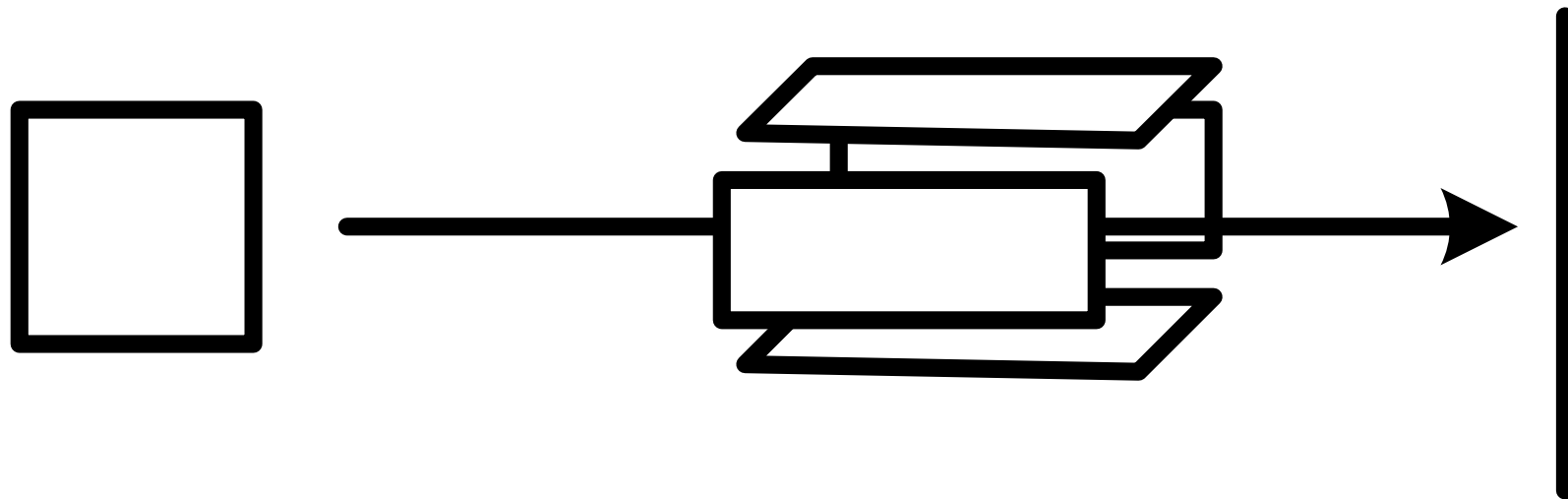
# Mask making

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Electron gun

Lens

Mask

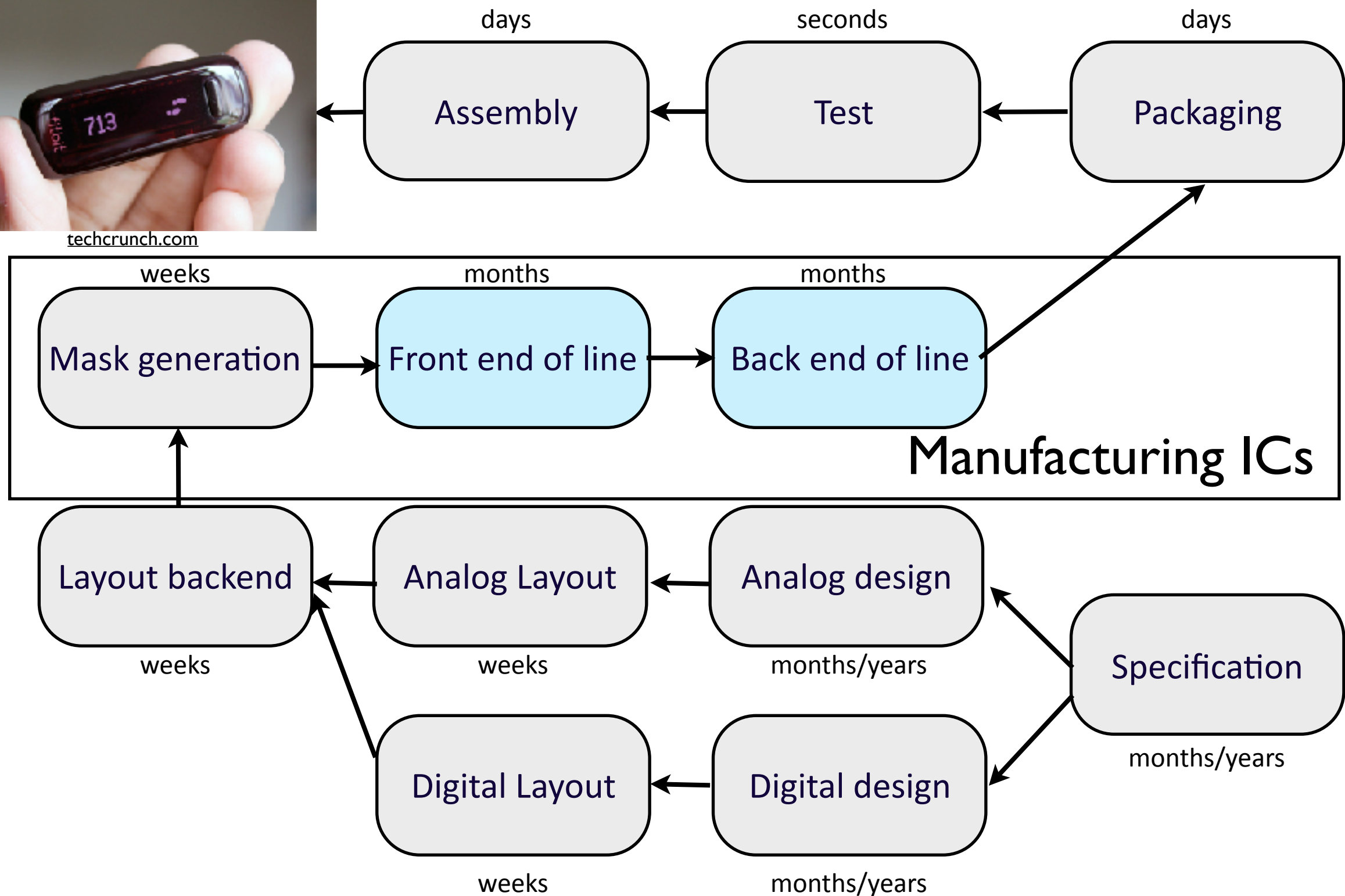


- Mask making is extremely expensive
- A normal chip has around 30 - 40 masks.
- At the 20nm node the mask cost is around 20 million NOK

# The complete story

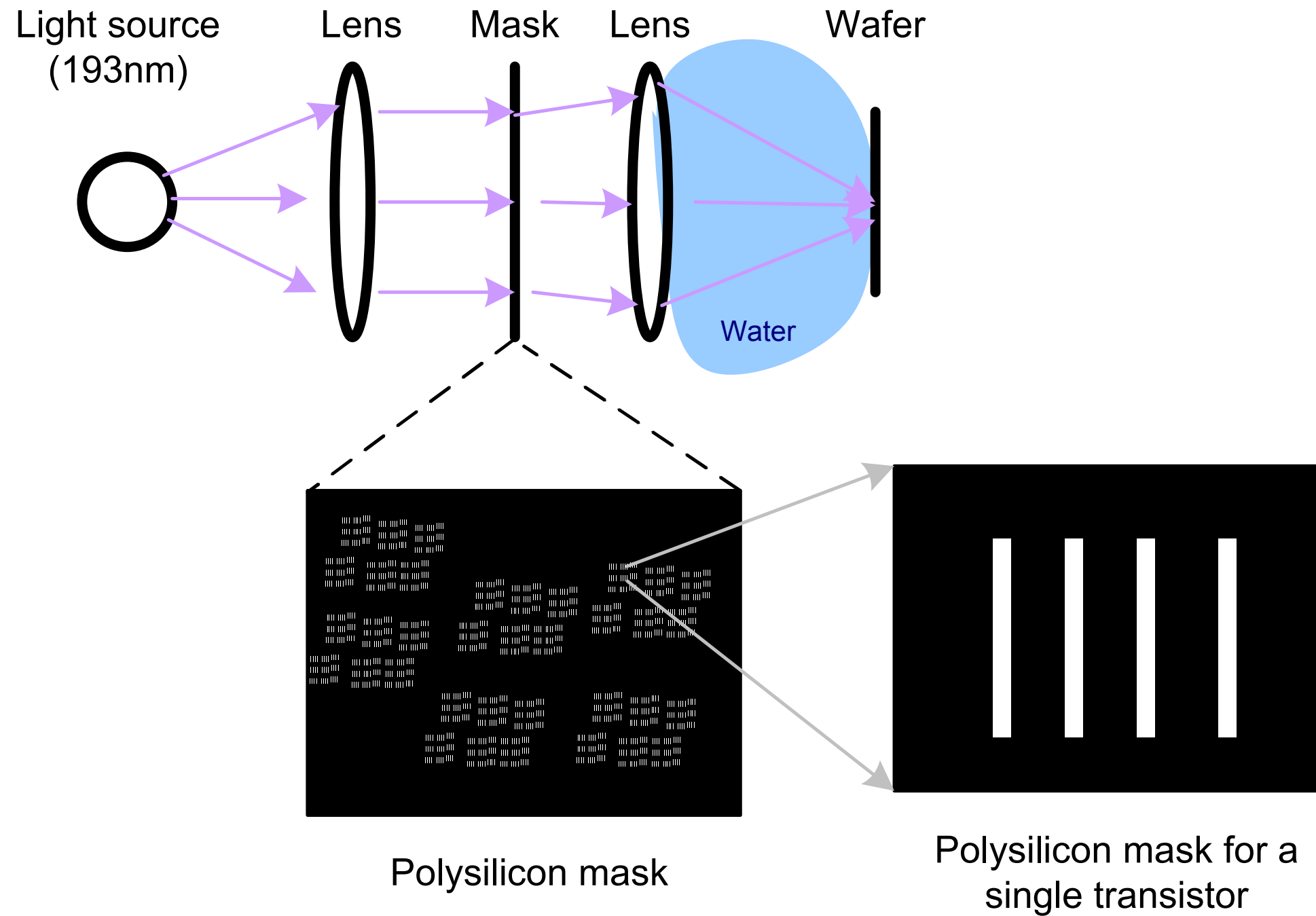


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# Lithography

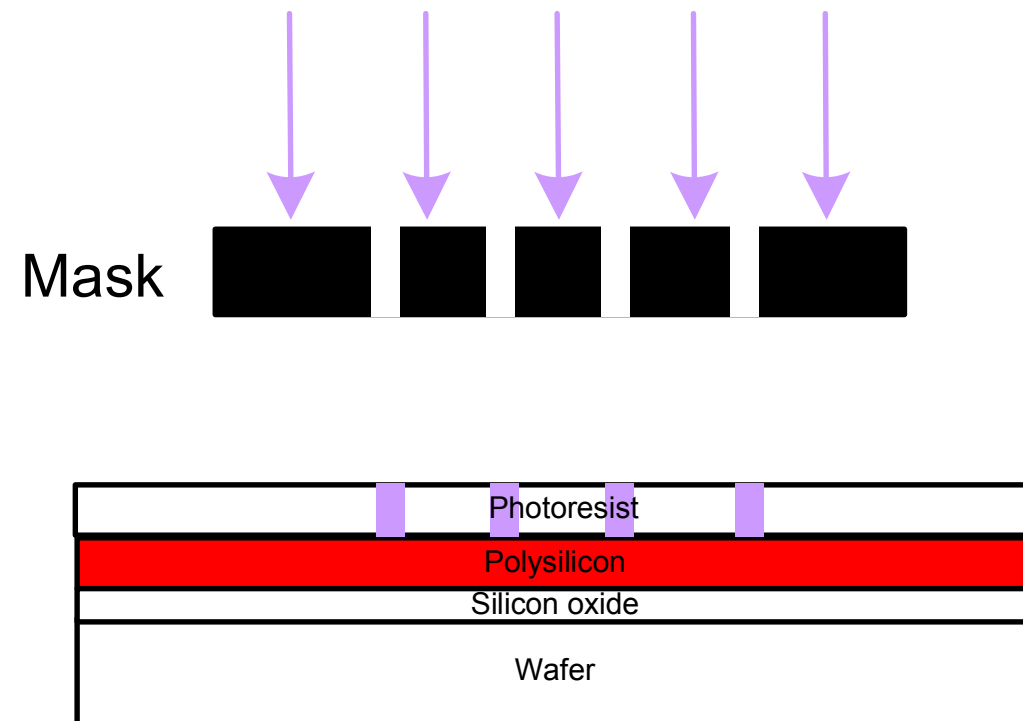
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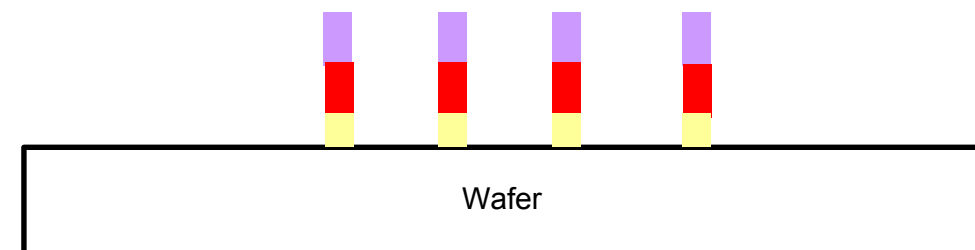
Lithography machines

# Photoresist and lithography

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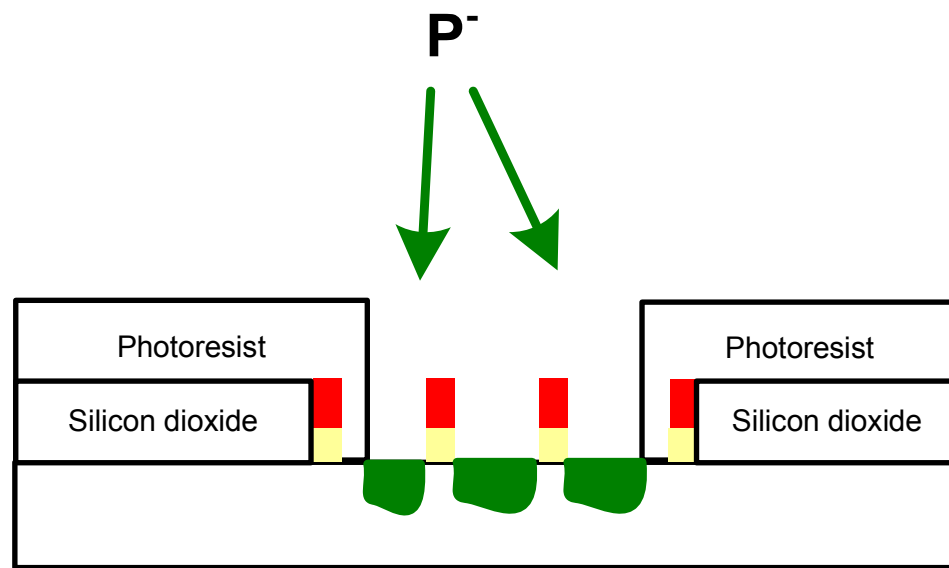
1) Expose photoresist



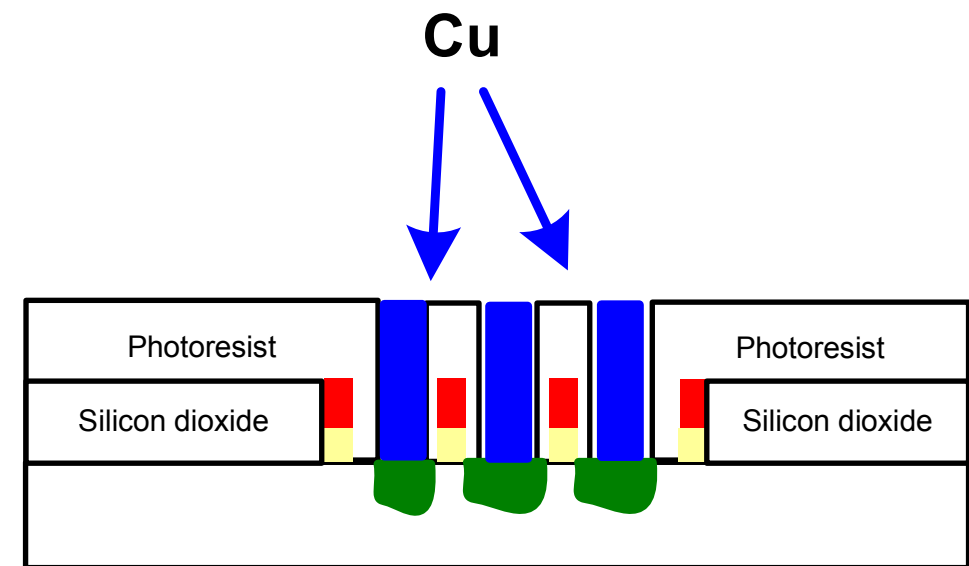
2) Remove photoresist and etch polysilicon

# Doping and metal

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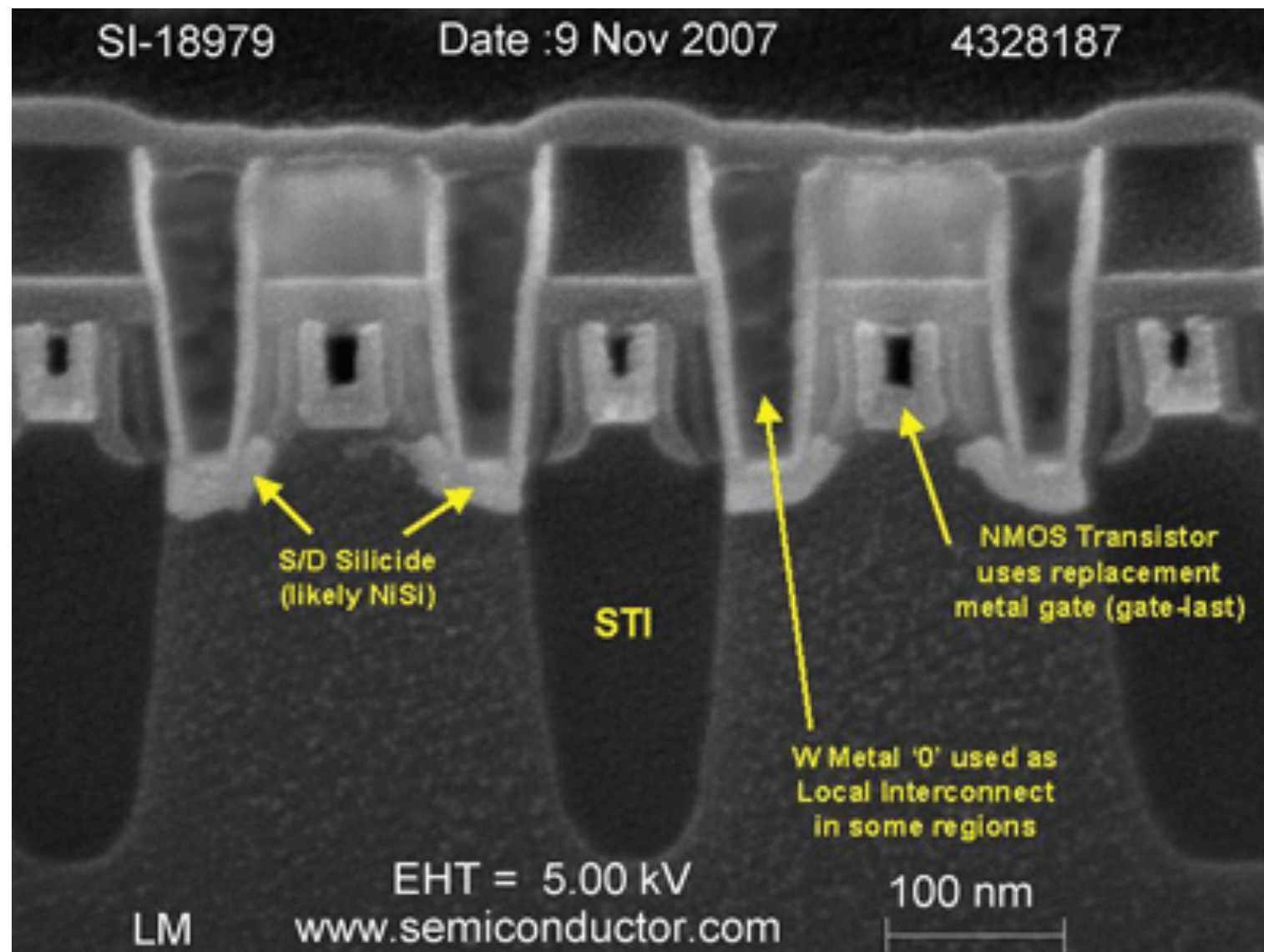
3) Add doping



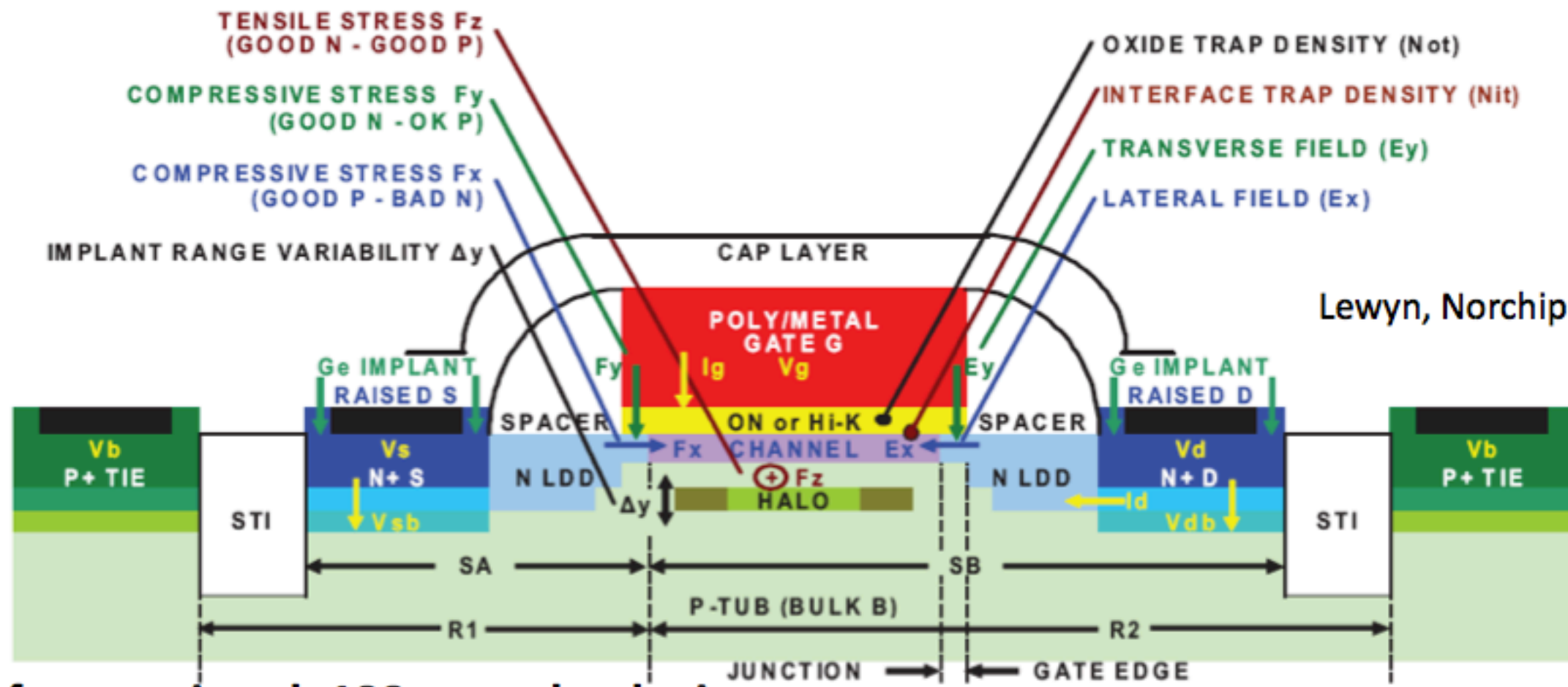
4) Add metal

# Making transistors

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# Nano-scale transistor



Lewyn, Norchip 2009



# Today: 193nm argon fluoride excimer laser

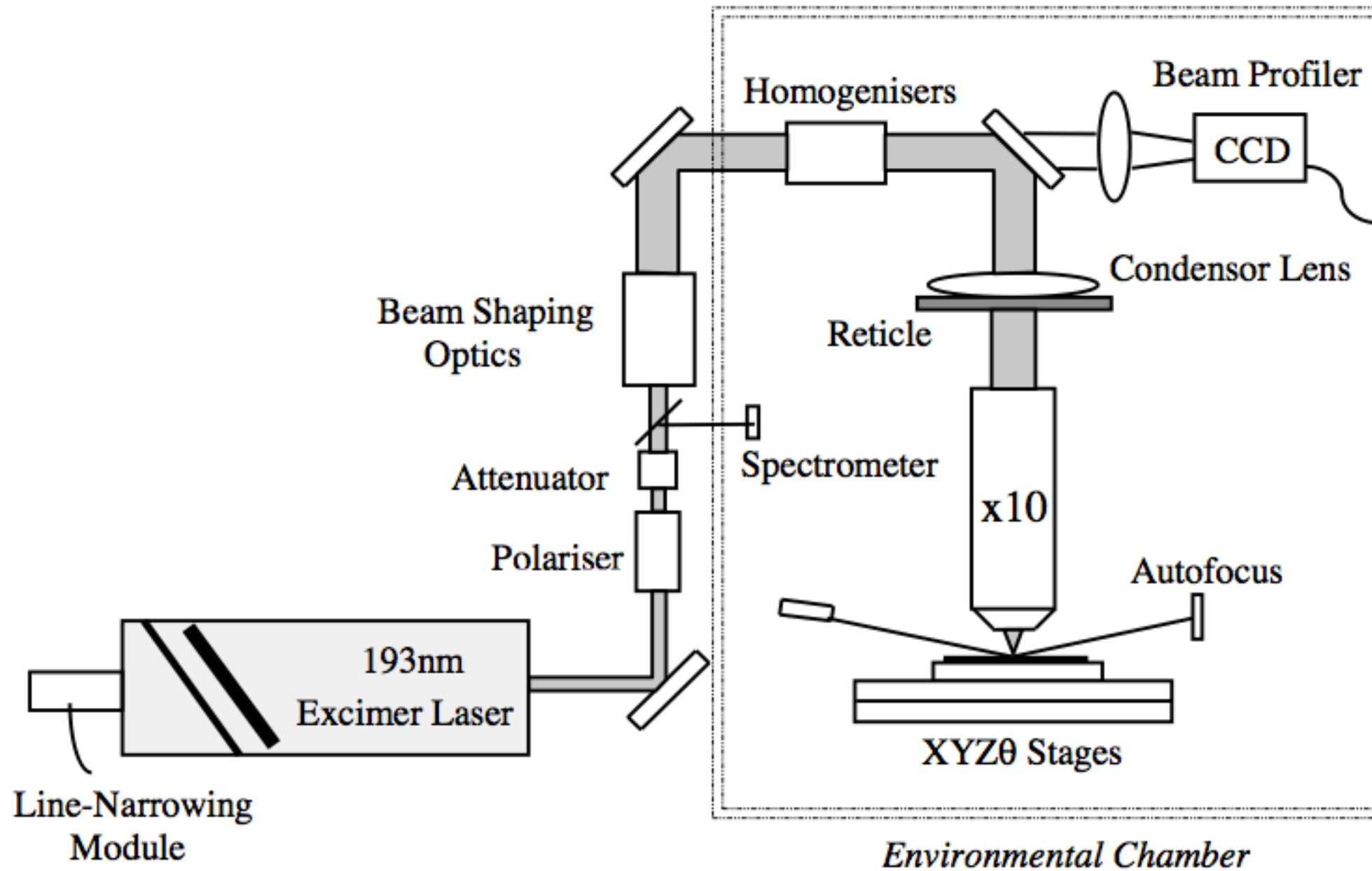
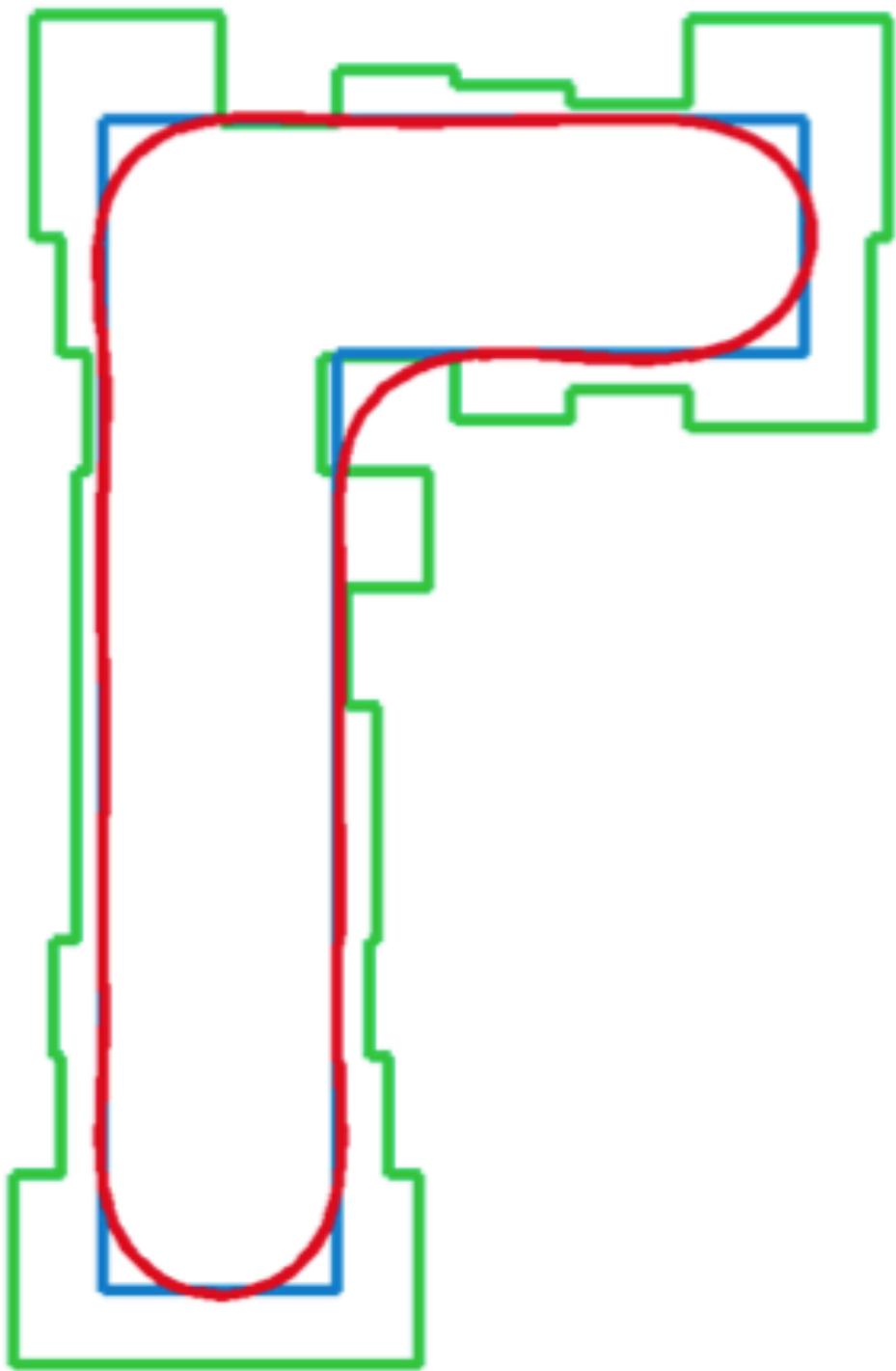


Figure 2. Schematic diagram of 193nm Microstepper

# Optical proximity correction

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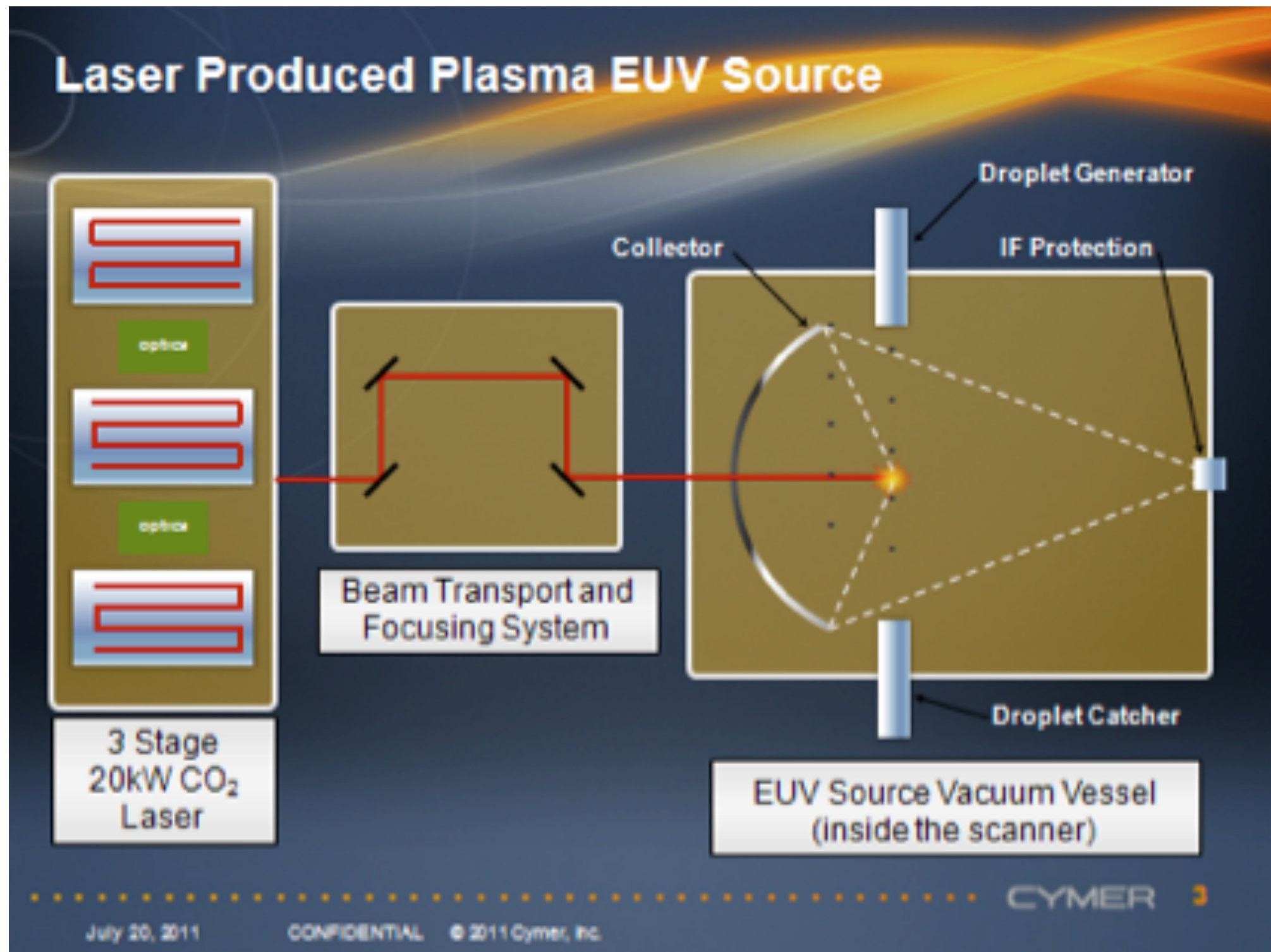
- The wavelength of the developing light is larger than minimum features (  $193\text{nm} > 20\text{nm}$  )
- Diffraction patterns affect the light intensity on the photo-resist
- Extensive calculations need to calculate how the mask should look to compensate for diffraction and processing inaccuracies

Blue = Pattern we draw in our CAD programs

Green = How the mask actually looks

Red = Pattern on chip

# Tomorrow (maybe): Extreme ultra violet



**“At least another decade”: What Next?**

# Topics not covered

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- Simulation, corner verification
- Digital design (Verilog)
- System level design (Matlab)
- Project management
- Lab testing
- Writing documentation
- Writing patents

What to focus on the  
next five years

# Divide and conquer

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- Break complex stuff into smaller pieces
- Ignore the difficult stuff, and try to get an approximate understanding, then add in the difficult stuff
- Don't be afraid if something is difficult
- Don't think you're stupid and won't be able to understand
- Don't think that everybody else is smarter than you

# What you need to teach yourself

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- Ability to work hard (constant speed)
- Ability to focus on the important stuff
- Programming
- Report writing
- Explaining things to other people



# Lesson 2

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Learn your courses, they are important